

ABSTRACT

This invention relates to an apparatus and method for positioning dual stages during semiconductor wafer processing. More particularly, the invention facilitates the use of
5 interferometers to determine the positions of both wafer stages at all times during processing. While the movement of a typical twin stage apparatus causes one of the stages to eclipse the other and requires the addition of a significant number of additional interferometers, this invention minimizes the number of interferometers necessary through dimensioning the stages so that one stage never totally eclipses the other.

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